

# Phonon confinement and excitonic absorption in the optical properties of ZnO films

Nuwanjula Samarasingha,<sup>1</sup> Stefan Zollner,<sup>1</sup> Dipayan Pal,<sup>2</sup> Aakash Mathur,<sup>2</sup> Ajaib Singh,<sup>2</sup> Rinki Singh,<sup>3</sup> Sudeshna Chattopadhyay<sup>2,3,4</sup>

<sup>1</sup>Department of Physics, New Mexico State University, Las Cruces, NM

<sup>2</sup>Discipline of Metallurgy Engineering and Materials Science, Indian Institute of Technology Indore, Indore 453552, India

<sup>3</sup>Discipline of Biosciences and Biomedical Engineering, Indian Institute of Technology Indore, Indore 453552, India

<sup>4</sup>Discipline of Physics, Indian Institute of Technology Indore, Indore 453552, India

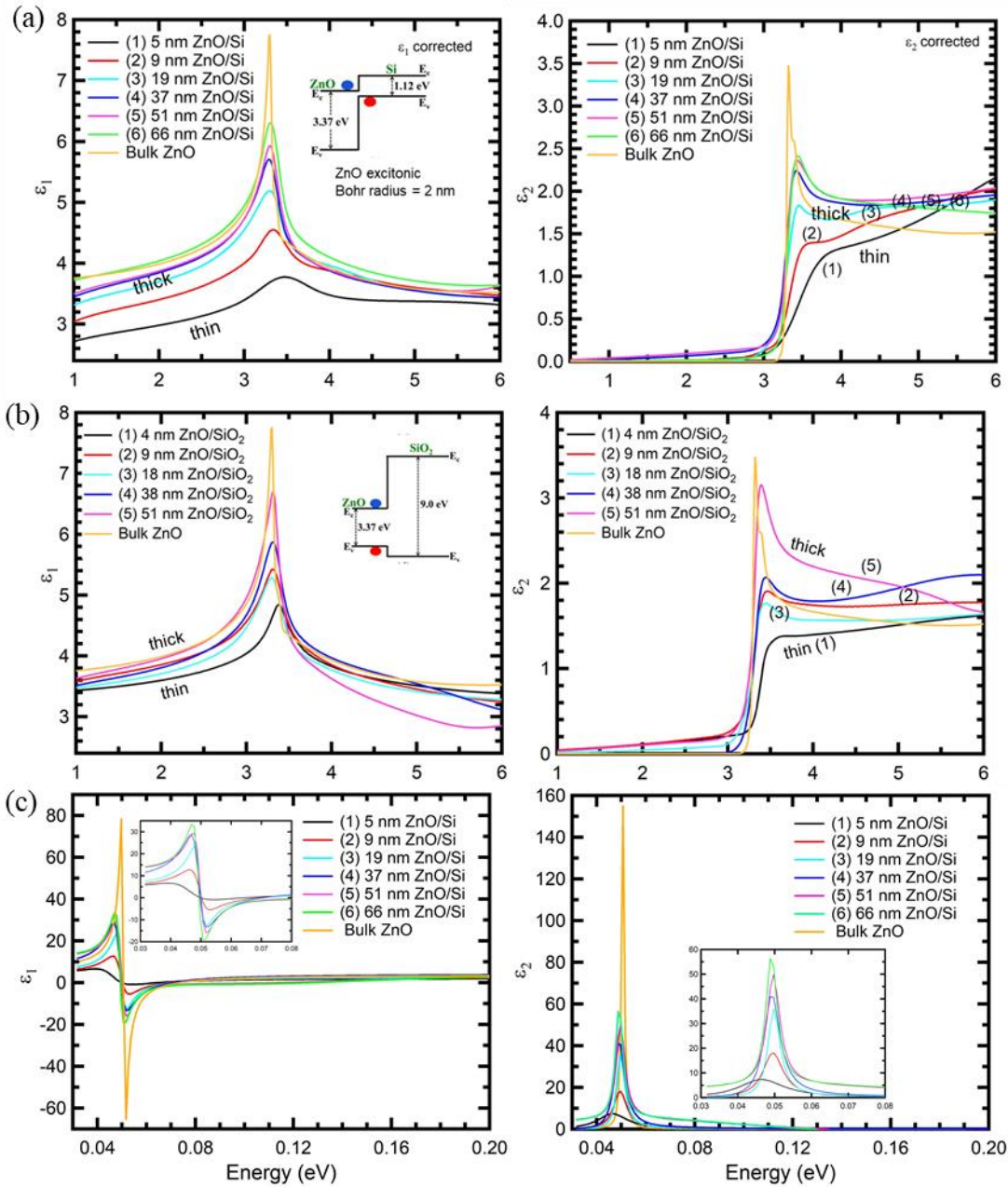


Fig: Real ( $\epsilon_1$ ) and imaginary part ( $\epsilon_2$ ) of the dielectric function vs film thickness of ZnO films on (a) Si (b)  $\text{SiO}_2$  substrates vs photon energy (1 – 6 eV) at 300K. (c)  $\epsilon_1$  and  $\epsilon_2$  vs film thickness of ZnO films on Si substrates vs photon energy (0.03 – 0.20 eV).